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**Electronic Supplementary Information** 

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## Localised Nanoscale Resistive Switching in GaP Thin Films with Low Power Consumption

Fran Kurnia,<sup>a</sup> Chunli Liu,<sup>b</sup> Guangqing Liu,<sup>a</sup> Rama K. Vasudevan,<sup>c</sup> Sang Mo Yang,<sup>c,d</sup> Sergei

V. Kalinin,<sup>c</sup> Nagarajan Valanoor<sup>a</sup> and Judy N. Hart<sup>a</sup>\*

<sup>a</sup> School of Materials Science and Engineering, UNSW Australia, UNSW Sydney 2052,

Australia

<sup>b</sup> Department of Physics and Oxide Research Center, Hankuk University of Foreign Studies,

Yongin 449-791, South Korea

<sup>c</sup> Center for Nanophase Materials Sciences, Oak Ridge National Laboratory, Oak Ridge,

Tennessee 37831, United States

<sup>d</sup> Department of Physics, Sookmyung Women's University, Seoul 04310, Korea

\*Corresponding author:

(Judy N. Hart) j.hart@unsw.edu.au

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Fig. S1. (a) Repeatable unipolar resistive switching over more than 20 cycles. (b) Cumulative probability of RESET and SET voltages.



Fig. S2. AFM topography image and line profile, taken at the position indicated by the black line in the AFM image.



Fig. S3. Sample structure and cAFM measurement setup.



Fig. S4. Current distribution over an island of GaP. The red cross marks the tip position used for *I-V* measurements.



Fig. S5. Fitting of the *I-V* curves using five different conduction mechanisms in both the ONand OFF-states. The best fits are obtained with the Frenkel-Poole emission mechanism for the OFF-state and the SCLC mechanism for the ON-state.



Fig. S6. Evolution of conduction map at the increasing bias voltage from 1 V to 6 V. The unit scale bar is in nA.



Fig. S7. *I-V* switching cycles averaged from the entire region of interest in Fig. S5.



Fig. S8. *I-V* characteristics of the GaP film in a well-ordered crystalline region of the film.